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U.S. PATENT DOCUMENTS

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FOREIGN PATENT DOCUMENTS

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OTHER DOCUMENTS

		Wei W. Lee, et al.; FABRICATION OF 0.06 μm POLY-Si GATE USING DUV LITHOGRAPHY WITH A DESIGNED $\text{Si}_x\text{O}_y\text{N}_z$ FILM AS AN ARC AND HARDMASK ; 1997 Symposium on VLSI Technology Digest of Technical Papers; pp. 131 & 132; 1997.
	Examiner 	Date Considered 9/27/01